

31 the burst characteristic and the spike characteristic by adding a trace quantity of xenon gas to the gas for ultraviolet laser in the chamber in Japanese Patent Application No. 11-23709. --

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IN THE ABSTRACT OF THE DISCLOSURE:

Please replace the abstract of the disclosure of the following rewritten paragraph:

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32 -- A buffer gas contained in a laser gas used for an ArF excimer laser mainly consists of He, and Xe is preferably added to the laser gas. Mixture piping divided by valves is disposed on piping running from a chamber to an excimer laser gas cylinder, the mixture piping and a Xe gas cylinder are connected, gas exhaust by a gas exhaust module and opening and closing of the valves are controlled by a gas controller to add a trace quantity of xenon gas to the excimer laser gas. Thus, to remedy a burst characteristic and a spike characteristic of the ultraviolet laser device by adding a trace quantity of xenon gas, the xenon gas can be supplied efficiently into the chamber without modifying existing laser gas supply equipment. --

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IN THE CLAIMS:

33 Please claims 1-7 without prejudice or disclaimer of the subject matter set forth therein. Please add the following new claims 8-14: